

Figure 3.4 (p. 144)

(a) Idealized equilibrium band diagram (energy versus distance) for a metal-semiconductor rectifying contact (Schottky barrier). The physical junction is at $x = 0$. (b) Charge at an idealized metal-semiconductor junction. The negative charge is approximately a delta function at the metal surface. The positive charge consists entirely of ionized donors (here assumed constant in space) in the depletion approximation. (c) Field at an idealized metal-semiconductor junction.

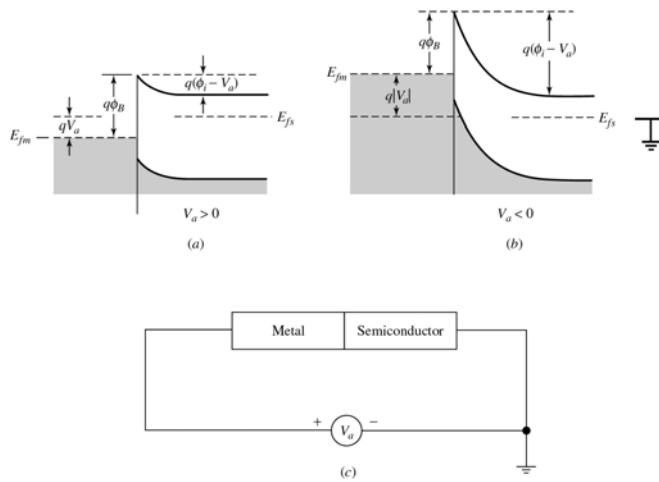
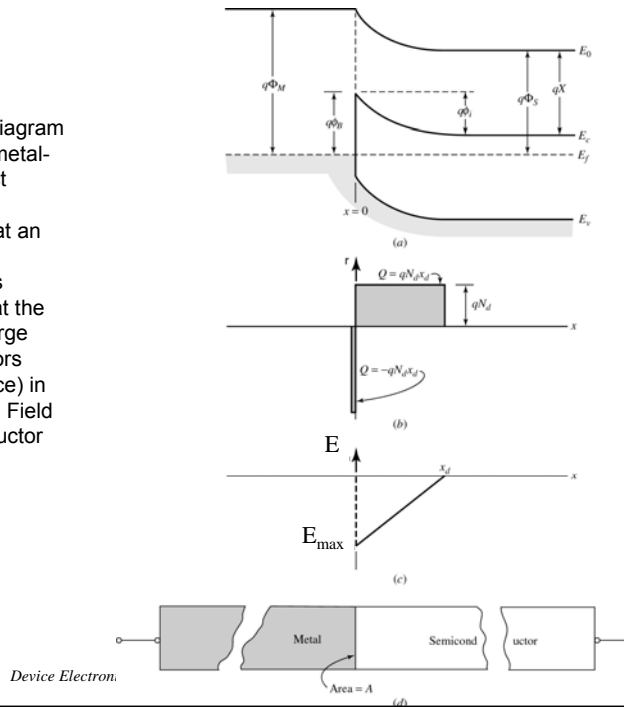


Figure 3.5 (p. 146)

Idealized band diagrams (energy versus distance) at a metal-semiconductor junction (a) under applied forward bias ($V_a > 0$) and (b) under applied reverse bias ($V_a < 0$). The semiconductor is taken as the reference (voltage ground) as shown in (c). The vacuum levels for the two cases are not shown.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

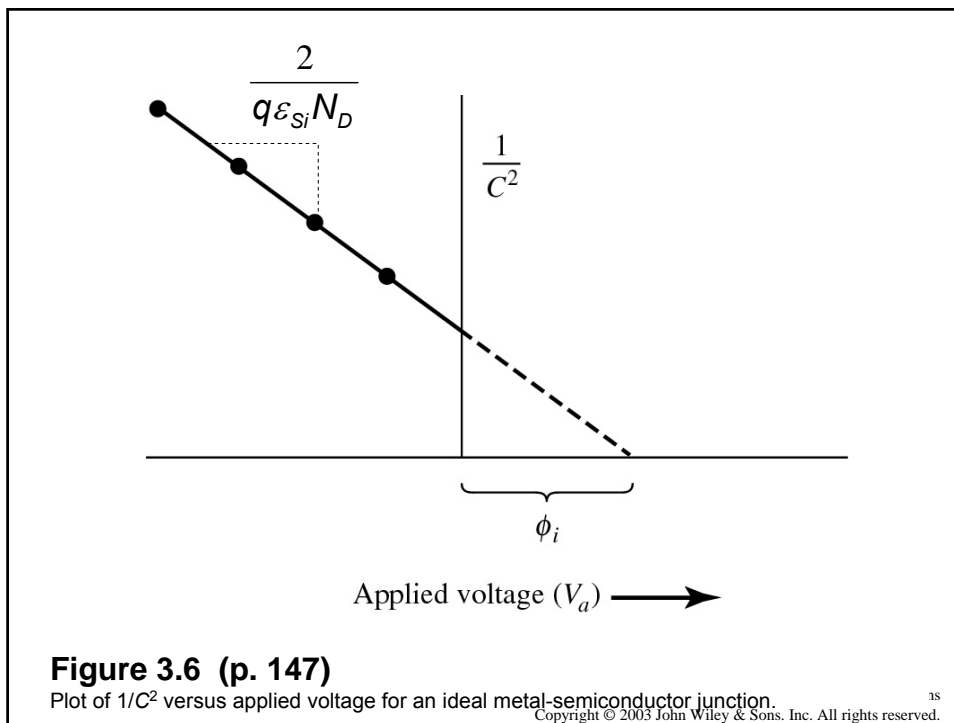
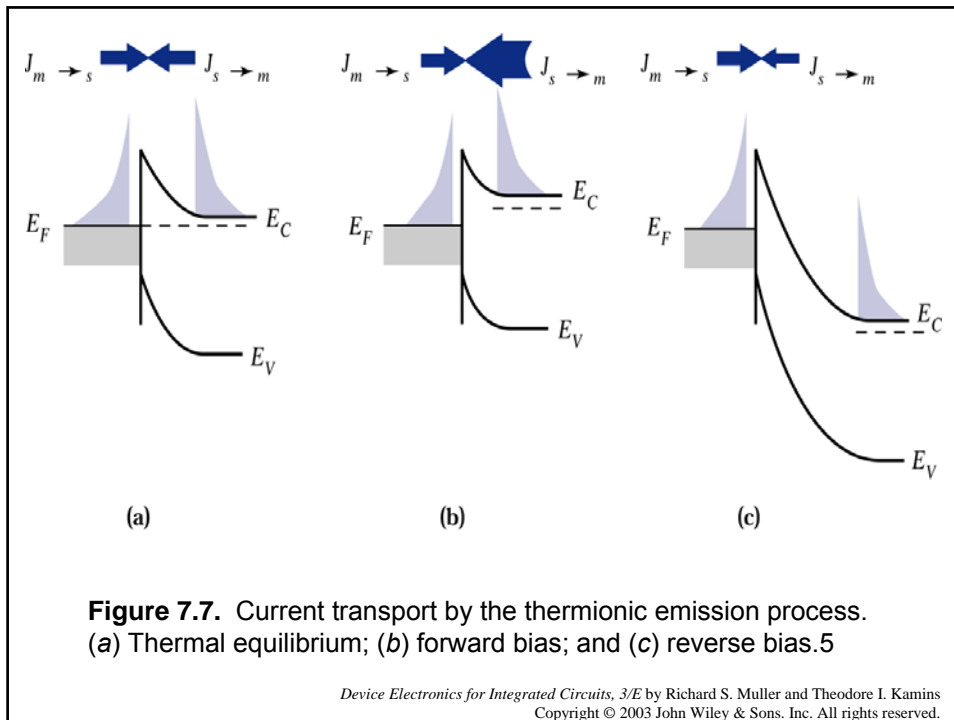


Figure 7.6.
 $1/C^2$ versus
 applied voltage
 for W-Si and
 W-GaAs
 diodes.

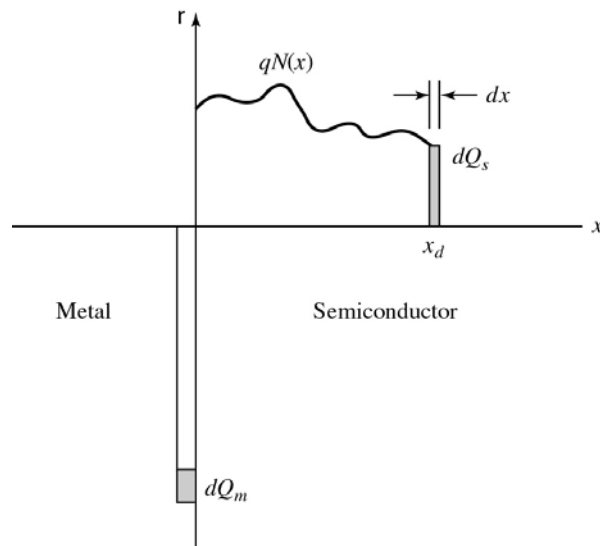
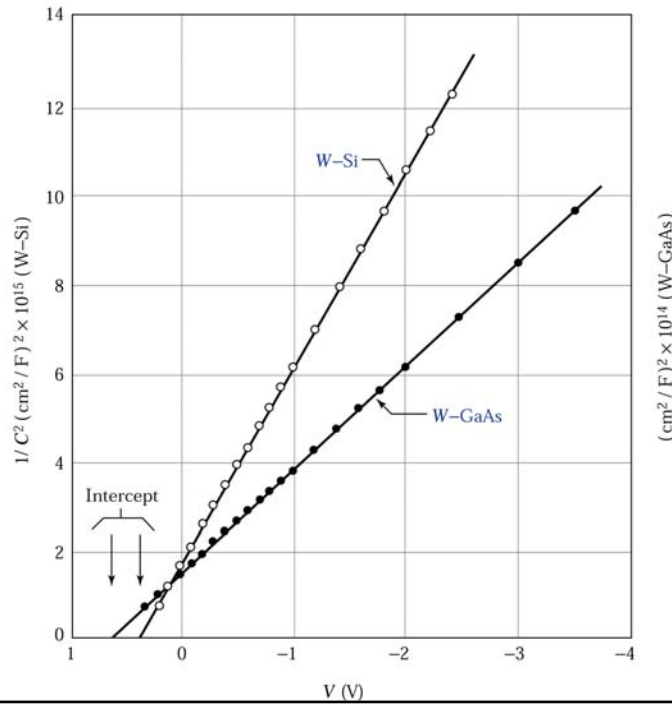


Figure 3.7 (p. 148)

Schematic representation of space charge at a metal-semiconductor junction with nonuniform doping in the semiconductor.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
 Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

Figure 7.8.
Forward current density versus applied voltage of W-Si and W-GaAs diodes.4

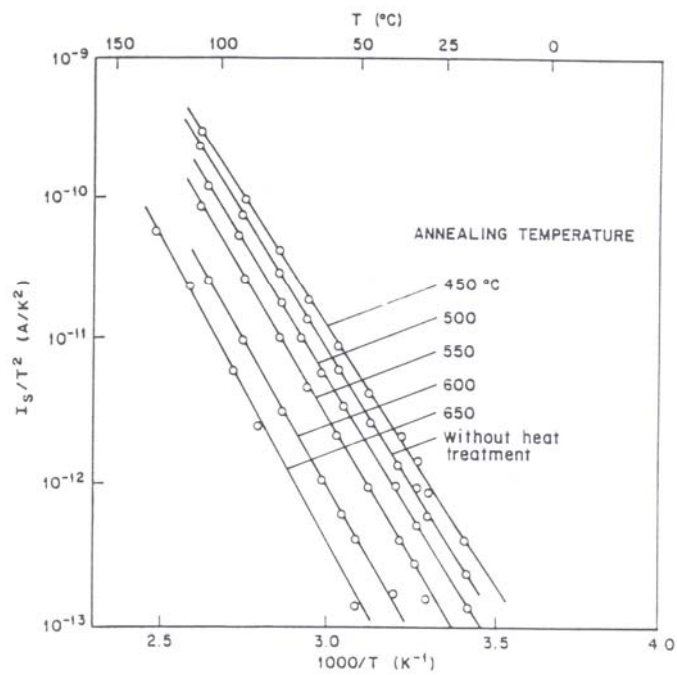
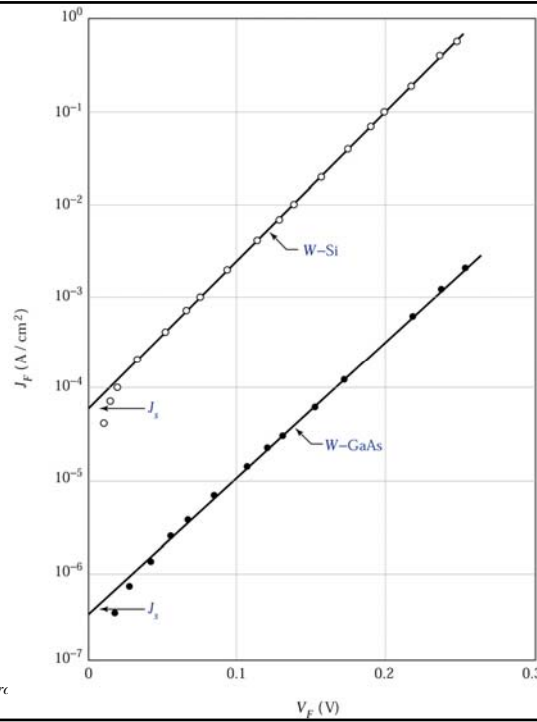
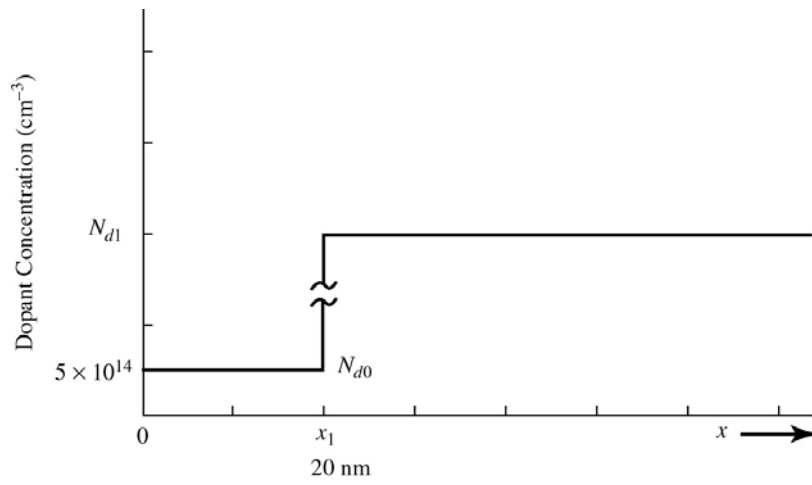
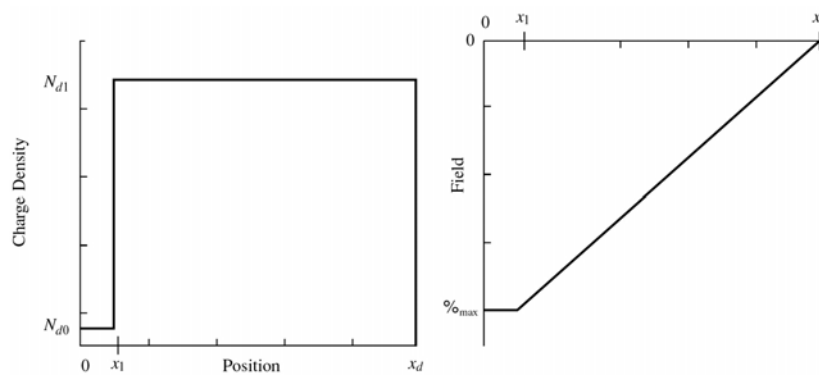


Fig. 27 Activation energy plots for determination of barrier height. (Alter Chino, Ref. 47.)



Example: Schottky Barrier Diode (p. 149)

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.



Example: Schottky Barrier Diode (cont., p. 150)

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

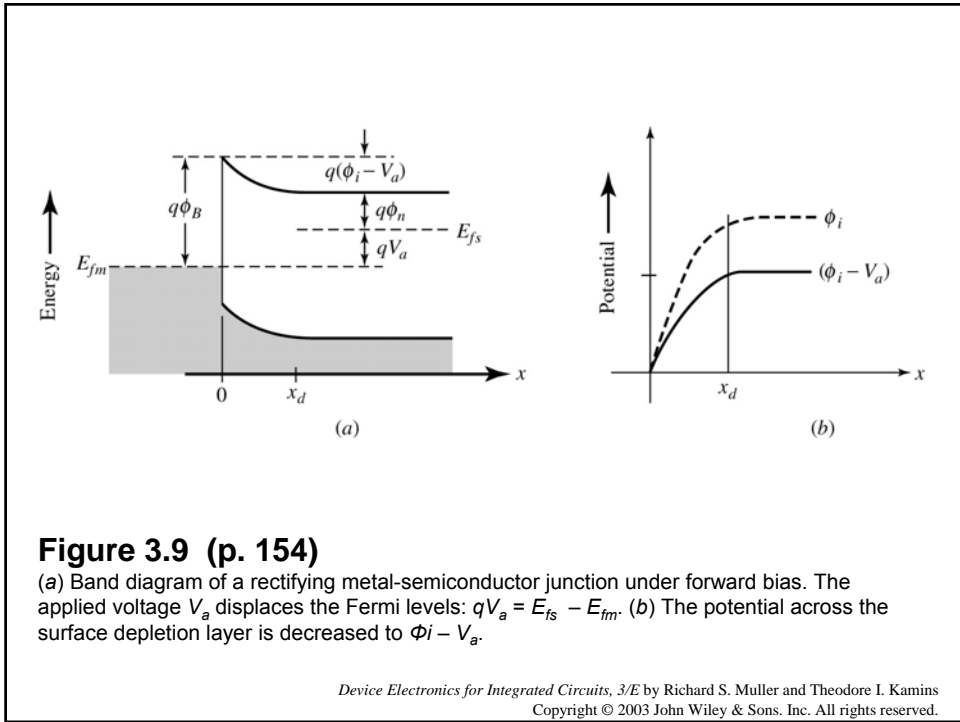
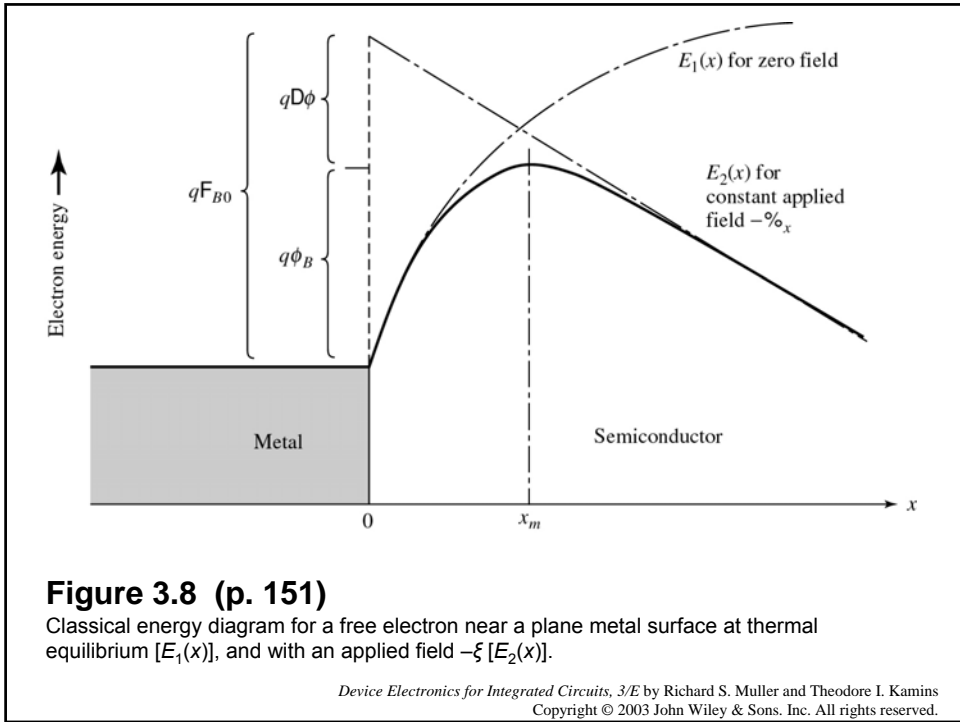
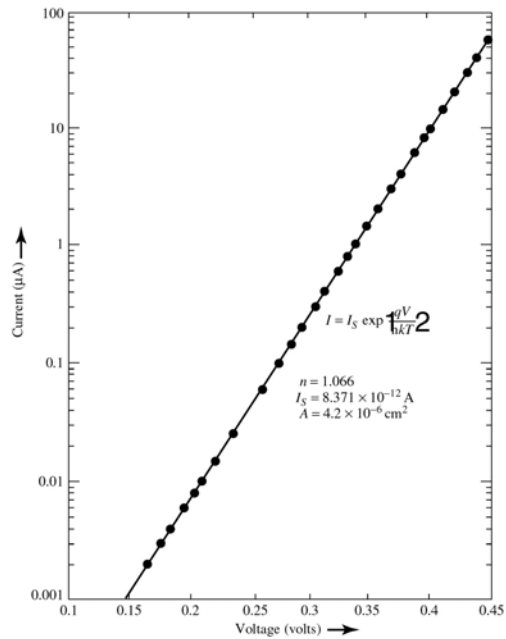


Figure 3.10 (p. 156)

Measured values of current (plotted on a logarithmic scale) versus voltage for an aluminum-silicon Schottky barrier. Values for $I_s = J_s A$ and n are obtained from an empirical fit of the data to Equation 3.3.17.



Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
 Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

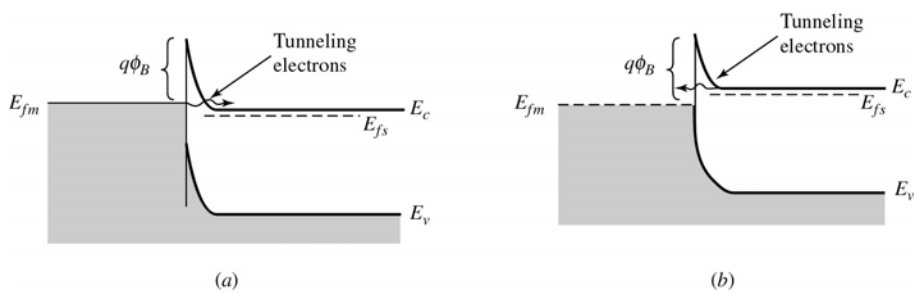
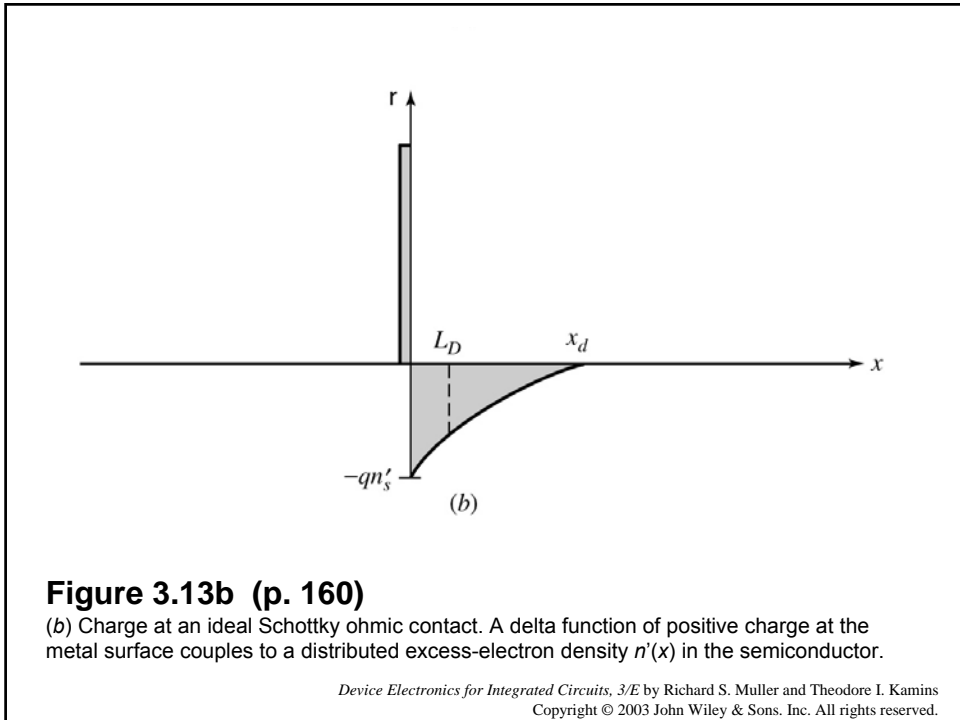
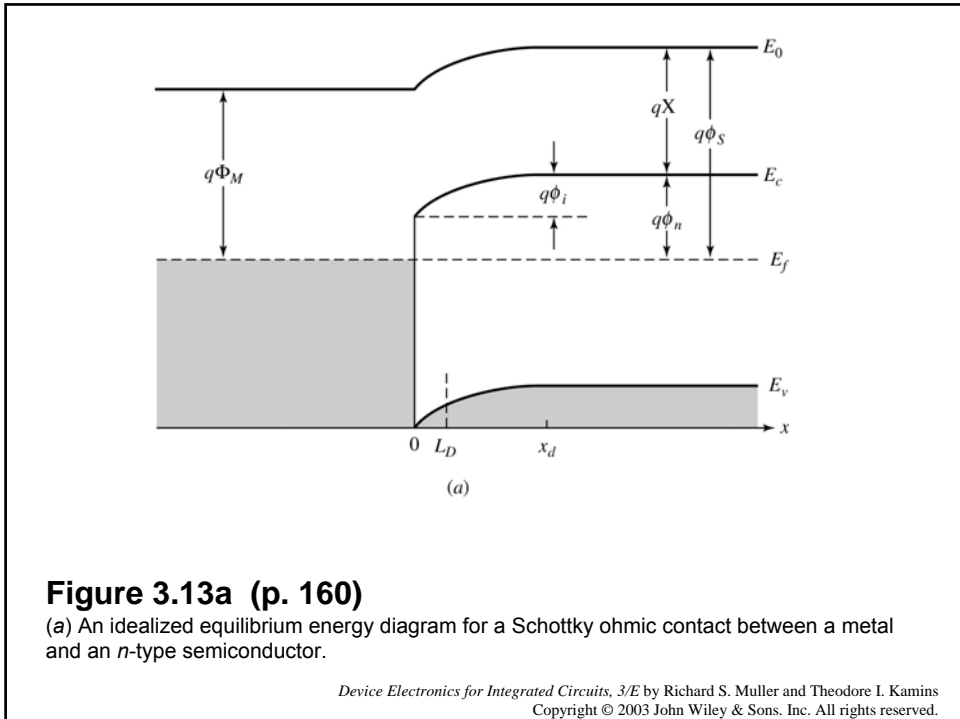


Figure 3.12 (p. 159)

Metal-semiconductor barrier with a thin space-charge region through which electrons can tunnel. (a) Tunneling from metal to semiconductor. (b) Tunneling from semiconductor to metal.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
 Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.



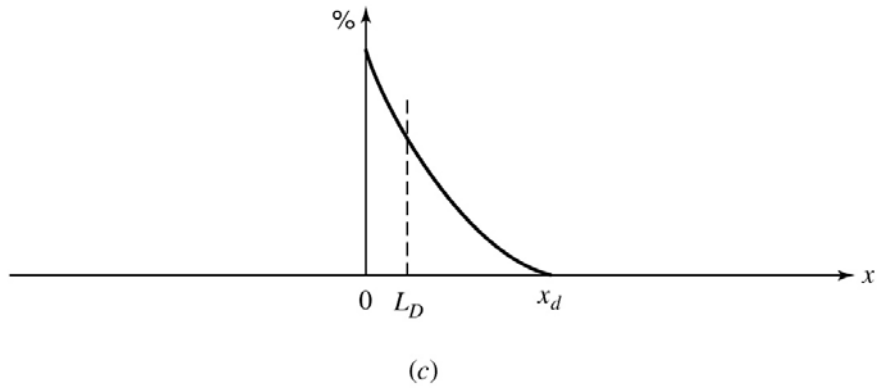


Figure 3.13b (p. 160)
(c) Field.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

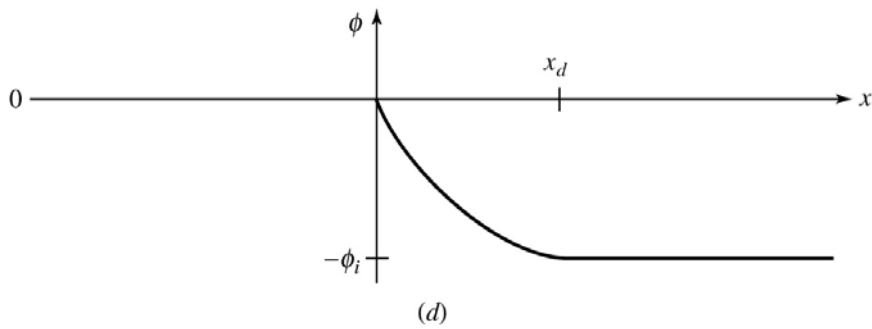
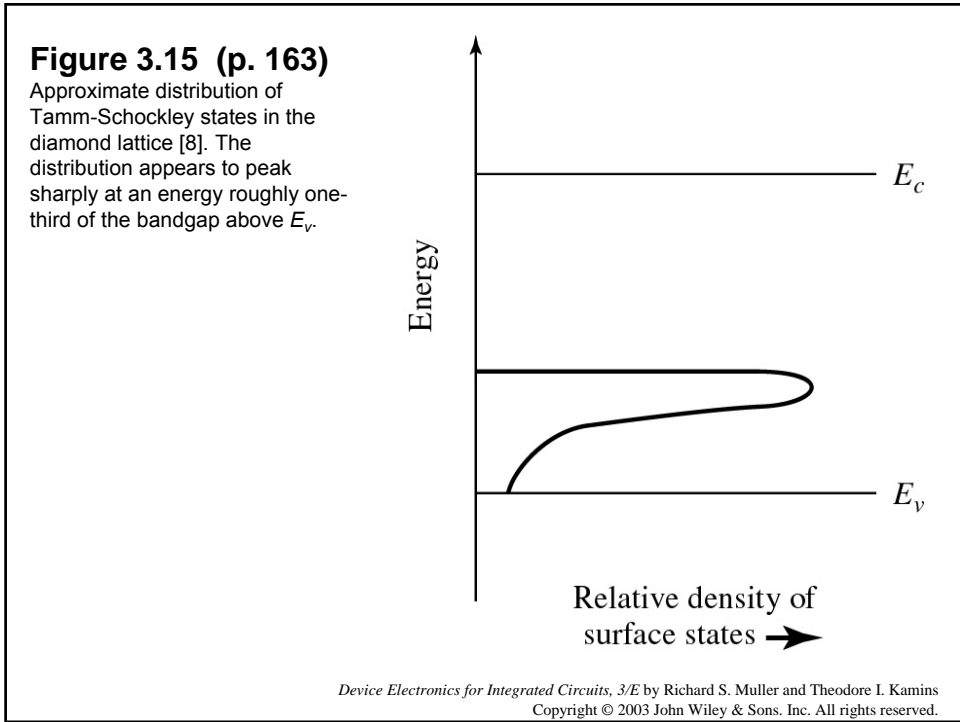
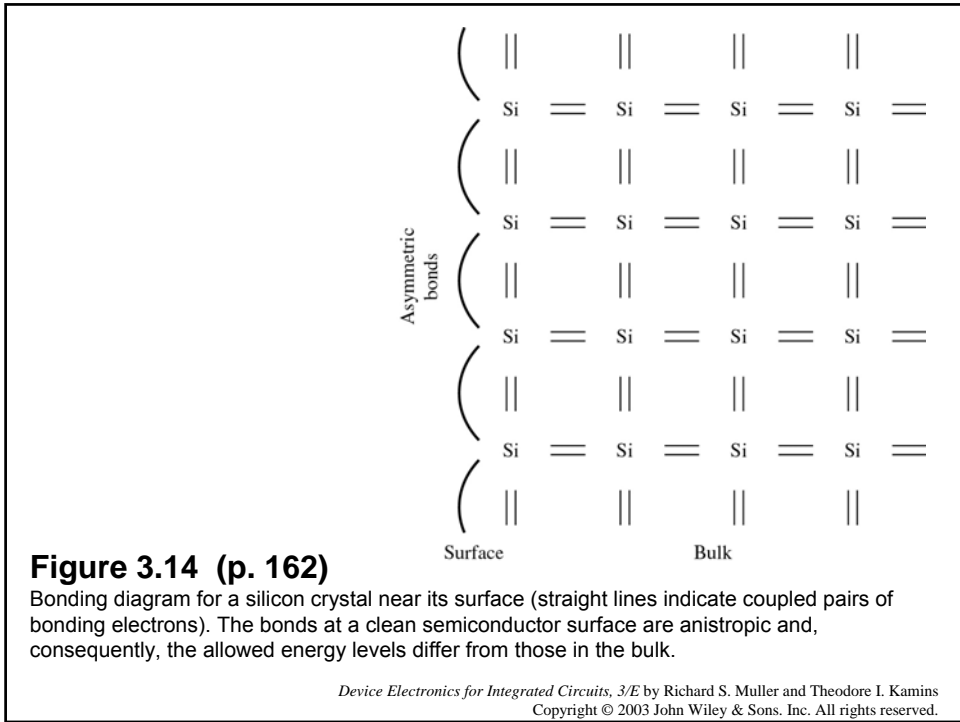
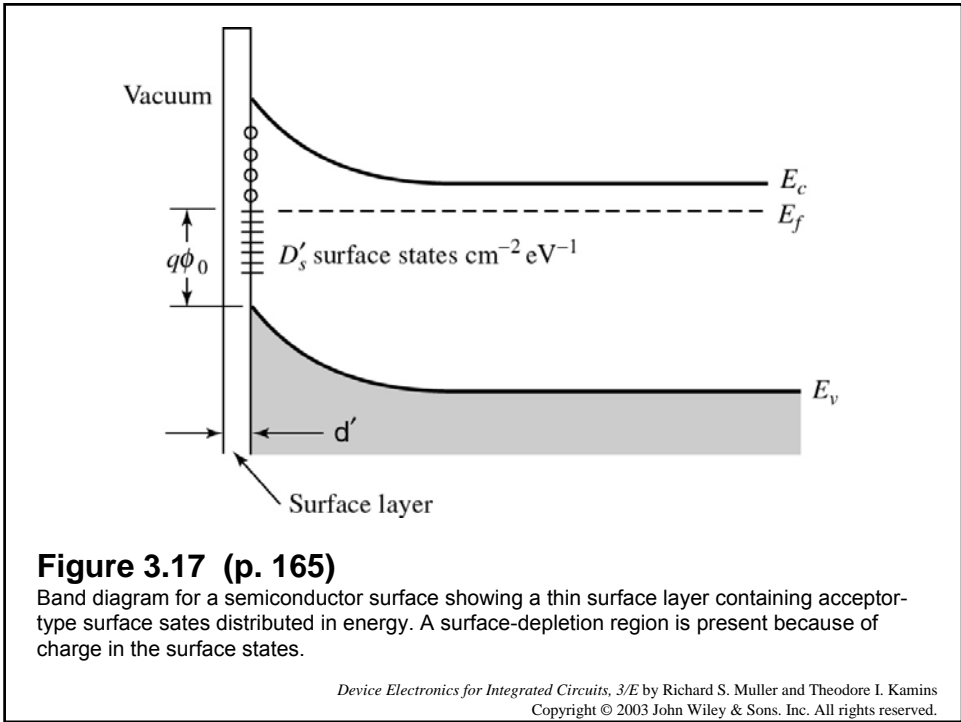
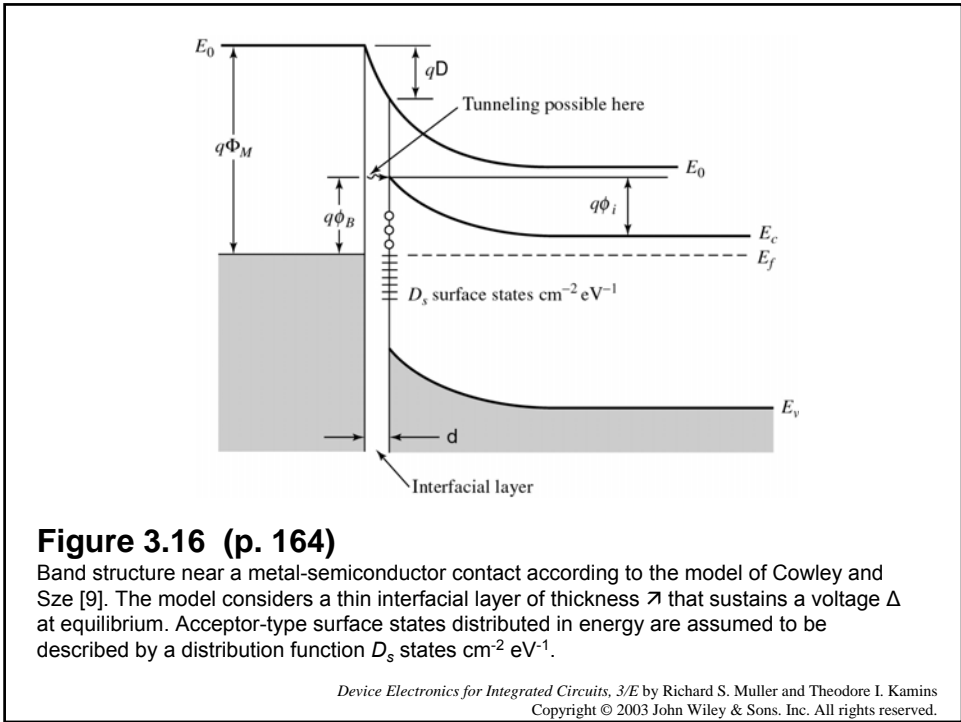


Figure 3.13c (p. 160)
(d) Potential at an idealized Schottky ohmic contact. The Debye length L_D is a characteristic measure of the extent of the charge and field.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.





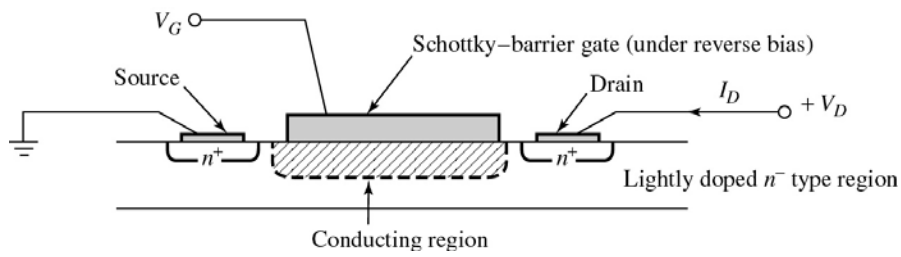


Figure 3.18 (p. 167)

Schottky-barrier-gate, field-effect transistor. Current I_D flowing from drain to source is modulated by gate voltage V_G that controls the dimensions of the depletion region. This, in turn, modulates the cross-sectional conducting area for I_D . The source and drain contacts are ohmic because they are made to highly doped material.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

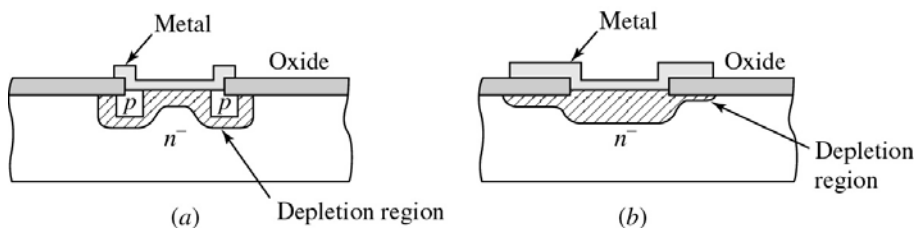


Figure 3.19 (p. 167)

Special processing techniques improve the performance of Schottky diodes shown here in cross section. (a) The diffused p -type guard ring leads to a uniform electric field and eliminates breakdown at the junction edges and corners. (b) The metal field plate is an alternative means for achieving the same effect.

Device Electronics for Integrated Circuits, 3/E by Richard S. Muller and Theodore I. Kamins
Copyright © 2003 John Wiley & Sons, Inc. All rights reserved.

